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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/052,815	01/18/2002	Phillip L. Wimmer	10012053-1	3187
7590 03/10/2006			EXAMINER	
HEWETT-PACKARD COMPANY Intellectual Property Administration		FULLER, ERIC B		
P.O. Box 272400			ART UNIT	PAPER NUMBER
Fort Collins, CO 80527-2400		1762		

DATE MAILED: 03/10/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)
	10/052,815	WIMMER ET AL.
Office Action Summary	Examiner	Art Unit
	Eric B. Fuller	1762
The MAILING DATE of this communication ap		<u>L</u>
Period for Reply		
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING E - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statuf Any reply received by the Office later than three months after the mailin earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATION 136(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from the, cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).
Status		
1) ☐ Responsive to communication(s) filed on 19 L 2a) ☐ This action is FINAL . 2b) ☐ This 3) ☐ Since this application is in condition for allowated closed in accordance with the practice under	s action is non-final. ance except for formal matters, pro	
Disposition of Claims		
4) ☐ Claim(s) 1-5,7-21,25,26 and 33-36 is/are pen- 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-5,7-21,25,26 and 33-36 is/are reje 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/e	awn from consideration.	
Application Papers		
9) The specification is objected to by the Examin	er.	
10) The drawing(s) filed on is/are: a) ac		Examiner.
Applicant may not request that any objection to the	e drawing(s) be held in abeyance. See	e 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	= : :	•
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Bureat* See the attached detailed Office action for a list	nts have been received. Its have been received in Applicationity documents have been received au (PCT Rule 17.2(a)).	on No ed in this National Stage
Attachment(s)		(DTO 440)
1) Motice of References Cited (PTO-892) 2) D Notice of Draftsperson's Patent Drawing Review (PTO-948)	4) Ll Interview Summary Paper No(s)/Mail Da	
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date		ratent Application (PTO-152)

DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on November 14, 2005 has been entered.

Response to Arguments

Applicant's amendments and supporting arguments have sufficiently overcome the rejections of the previous Office Action. Those rejections have been withdrawn accordingly. Applicant's arguments are most in view of the new grounds of rejection.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1, 2, 10, 11, 18, 19, and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Slysh (US 5,147,680) in view of Taylor et al. (J. Appl. Phys 64 (5)).

Application/Control Number: 10/052,815

Art Unit: 1762

Slysh teaches to roughen a substrate by irradiating the surface with a laser in order to increase the adhesion of a layer to be applied (abstract). A mask may be used to control the areas on ablation (column 2, lines 15-30). The reference is silent to resettling the ablation debris.

However, Taylor teaches that by selecting the laser fluence, some of the debris is re-deposited on to the substrate. The debris then collects in areas due to electrostatic forces, function as a mask, and allow for the rcreation of conical morphology. This conical morphology increases the surface area capable for bonding between the substrate and the adhesion layer. From this, it would have been obvious at the time the invention was made to a person having ordinary skill in the art to control the laser fluence in the process taught by Slysh such that debris resettles on to the substrate and functions as a mask. By doing so, one would reap the benefits of increased surface area for bonding.

Claims 1, 2, 10, 11, 18, 19, and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Slysh (US 5,147,680) in view of Owen et al. (US 5,593,606).

Slysh teaches to roughen a substrate by irradiating the surface with a laser in order to increase the adhesion of a layer to be applied (abstract). A mask may be used to control the areas on ablation (column 2, lines 15-30). The reference is silent to resettling the ablation debris.

However, Owen teaches that by using a solid-state laser, the debris resettles and functions as a mask. This allows for more precise cuts by the laser despite fluctuations

Application/Control Number: 10/052,815

Art Unit: 1762

in the power of the laser (column 13, lines 32-49). From this, it would have been obvious at the time the invention was made to a person having ordinary skill in the art to use a solid-state laser in the process taught by Slysh such that debris resettles on to the substrate and functions as a mask. By doing so, one would reap the benefits of more precise cuts.

Claims 1-5, 7-21, 25, 26 and 33-36 are rejected under 35 U.S.C. 103(a) as being unpatentable over Drazl et al. (US 6,565,927 B1) in view of Taylor et al. (J. Appl. Phys 64 (5)).

Drazl teaches to pattern a substrate by irradiating the surface with UV light in order to increase the adhesion of a layer to be applied (column 3, lines 1-25). The water, ozone, organic particles taught in column 3, lines 28-45 reads on being the initiator. The reference is silent to the optical energy being in the form of a laser.

However, Taylor teaches that by using a laser and selecting the laser fluence, some of the debris is re-deposited on to the substrate. The debris then collects in areas due to electrostatic forces, function as a mask, and allow for the rcreation of conical morphology. This conical morphology increases the surface area capable for bonding between the substrate and the adhesion layer. From this, it would have been obvious at the time the invention was made to a person having ordinary skill in the art to use a controlled laser in the process taught by Drazl such that debris resettles on to the substrate and functions as a mask. By doing so, one would reap the benefits of increased surface area for bonding.

Claims 1-5, 7-21, 25, 26 and 33-36 are rejected under 35 U.S.C. 103(a) as being unpatentable over Drazl et al. (US 6,565,927 B1) in view of Owen et al. (US 5,593,606).

Drazl teaches to pattern a substrate by irradiating the surface with UV light in order to increase the adhesion of a layer to be applied (column 3, lines 1-25). The water, ozone, organic particles taught in column 3, lines 28-45 reads on being the initiator. The reference is silent to the optical energy being in the form of a laser.

However, Owen teaches that by using a solid-state laser, the debris resettles and functions as a mask. This allows for more precise cuts despite fluctuations in power (column 13, lines 32-49). From this, it would have been obvious at the time the invention was made to a person having ordinary skill in the art to use a solid-state laser in the process taught by Drazl such that debris resettles on to the substrate and functions as a mask. By doing so, one would reap the benefits of more precise cuts.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Eric B. Fuller whose telephone number is (571) 272-1420. The examiner can normally be reached on Mondays through Thursdays.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tim Meeks, can be reached on (571) 272-1423. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Application/Control Number: 10/052,815 Page 6

Art Unit: 1762

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

EBF

TIMOTHY MEEKS
BUBERURORY PATENT EXAMINER